

| L Number | Hits | Search Text | DB | Time stamp |
|----------|---------|--|---|---------------------|
| 1 | 2 | ("6665562").PN. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/10/31 15:21 |
| 2 | 2 | ("6772040").PN. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/10/31 15:30 |
| 3 | 2 | ("6777654").PN. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/10/31 15:46 |
| 4 | 5 | ("6700090").PN. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/10/31 15:50 |
| 5 | 15234 | plasma near processing | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/10/31 15:50 |
| 6 | 2052855 | substrate or wafer | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/10/31 15:51 |
| 7 | 1 | modulat\$ near period\$ near ((high adj frequency)near voltage) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/10/31 15:57 |
| 8 | 85 | modulat\$ near period\$ and ((high adj frequency)near voltage) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/10/31 16:00 |
| 9 | 119085 | 219/\$.ccls. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/10/31 16:01 |
| 10 | 3 | (plasma near processing) and (modulat\$ near period\$ and ((high adj frequency)near voltage)) and 219/\$.ccls. | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/10/31 16:01 |